



## China Supply Best price 99.9% High Purty Hcds Si2cl6 Hexachlorodisilane

Our Product Introduction

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### Basic Information

- Place of Origin: China
- Brand Name: CMC
- Certification: COA
- Model Number: Si2cl6
- Minimum Order Quantity: 1kg
- Price: US \$40/kg
- Packaging Details: Cylinder/Tank
- Delivery Time: 15 days
- Payment Terms: L/C, T/T
- Supply Ability: 50000kg/month



### Product Specification

- Model NO.: Hexachlorodisilane
- Model No.: Si2cl6
- Transport: By Sea
- Purity: 99.9%
- Specification: 40L, 200L
- Trademark: CMC
- Origin: China
- HS Code: 2812190091
- Supply Ability: 100t/Year
- CAS No.: 7783-82-6
- Formula: Si2cl6
- EINECS: 7783-82-6
- Constituent: Industrial Pure Air
- Grade Standard: Industrial Grade
- Chemical Property: Poisonous Gases



### More Images



## Product Description

### Product Description

Si<sub>2</sub>Cl<sub>6</sub> gas refers to hexachlorodisilane, an inorganic compound composed of two silicon (Si) atoms bonded with six chlorine (Cl) atoms.

Hexachlorodisilane is typically encountered as a volatile liquid, but it can also exist in a gaseous state under specific conditions. Here are some key points about Si<sub>2</sub>Cl<sub>6</sub> gas:

**Structure and Properties:** Si<sub>2</sub>Cl<sub>6</sub> has a tetrahedral molecular structure, with two silicon atoms at the center and six chlorine atoms surrounding them. It is a reactive and volatile compound. Si<sub>2</sub>Cl<sub>6</sub> has a boiling point of approximately 147 °C (297 °F) and a molecular weight of 268.81 g/mol.

**Synthesis and Production:** Si<sub>2</sub>Cl<sub>6</sub> can be synthesized by reacting silicon tetrachloride (SiCl<sub>4</sub>) with silicon powder or elemental silicon (Si) at high temperatures. It can also be obtained by the reaction of silicon with chlorine gas (Cl<sub>2</sub>). The synthesis process typically occurs in a controlled environment to ensure safety and efficient production.

**Applications:**

**Chemical Synthesis:** Si<sub>2</sub>Cl<sub>6</sub> is used as a precursor or starting material in the synthesis of various silicon-based compounds. It is particularly employed in the production of organosilanes, which find applications in areas such as the production of specialty chemicals, coatings, adhesives, and sealants.

**Semiconductor Industry:** Si<sub>2</sub>Cl<sub>6</sub> is utilized in the fabrication of semiconductors and integrated circuits. It serves as a precursor in chemical vapor deposition (CVD) processes to deposit silicon-containing films, such as silicon carbide (SiC) or silicon nitride (Si<sub>3</sub>N<sub>4</sub>). These films are important for insulation, passivation, or dielectric purposes in semiconductor devices.

**Safety Considerations:** Si<sub>2</sub>Cl<sub>6</sub> is a reactive and volatile compound. It is important to handle it with caution and follow appropriate safety procedures when working with Si<sub>2</sub>Cl<sub>6</sub> gas or any other hazardous chemicals. Safety measures, including proper ventilation, personal protective equipment, and adherence to handling guidelines, should be followed to ensure safe usage.

Si<sub>2</sub>Cl<sub>6</sub> gas, or hexachlorodisilane, plays a significant role as a precursor in the production of silicon-containing compounds and semiconductor materials. Its reactivity and versatility make it valuable in various industrial applications. However, proper safety protocols should be observed to mitigate risks associated with its usage.

#### Basic Info.

Model NO.	Si <sub>2</sub> Cl <sub>6</sub>	Grade Standard	Electron Grade
Transport Package	Cylinder, Canister	Specification	40L, 200L
Trademark	CMC	Origin	Suzhou, China
HS Code	2812190091	Production Capacity	100t/Year

#### Specifications:

<b>IUPAC name</b>	Hexachlorodisilane
<b>Other names</b>	Disilicon hexachloride
<b>Identifiers</b>	
<b>CAS No.:</b>	13465-77-5
<b>EC No.:</b>	236-704-1
<b>Properties</b>	
<b>Molecular Formula:</b>	Si <sub>2</sub> Cl <sub>6</sub>
<b>Molar mass:</b>	268.88 g/mol
<b>Appearance:</b>	Colorless liquid
<b>Melting point:</b>	≤20 °C
<b>Boiling point:</b>	144 °C (291 °F; 417 K)
<b>Flash point:</b>	>93°C
<b>Vapor density(Air=1):</b>	>1
<b>Relative density(Water=1):</b>	1.562

#### Sample Test:

Test Items	Units	Specifications	Test Result
<b>Assay by GC</b>	wt%	≥99.9	99.905
<b>Li</b>	ng/g	≤0.5	<0.05
<b>Na</b>	ng/g	≤0.5	<0.05
<b>Mg</b>	ng/g	≤0.5	<0.05
<b>Al</b>	ng/g	≤1.0	0.35
<b>K</b>	ng/g	≤0.5	0.08
<b>Ca</b>	ng/g	≤0.5	0.16
<b>Ti</b>	ng/g	≤1.0	0.18
<b>Cr</b>	ng/g	≤0.5	<0.05
<b>Mn</b>	ng/g	≤0.5	<0.05
<b>Fe</b>	ng/g	≤1.0	0.48
<b>Co</b>	ng/g	≤0.5	<0.05

Ni	ng/g≤0.5	0.06
Cu	ng/g≤0.5	<0.05
Zn	ng/g≤0.5	<0.05

#### Detailed Photos





Shanghai Kemike Chemical Co., Ltd is staffed by trained personnel, combine many years experience in Gas industry .We supply cylinder gas, electronic gas, etc ., and the gas holder, panel, valves and fittings and other equipment, parts and engineering services to our customers in China and worldwide; The products are involved in various industrial fields, such as semiconductor chip, solar cell, LED, TFT-LCD, optical fiber, glass, laser, medicine , etc., Our mission is to partner with our global customers to provide support, solutions and quality products that are innovative, reliable, and safe. Our products mainly include: H<sub>2</sub>, O<sub>2</sub>, N<sub>2</sub>, Ar, CO<sub>2</sub>, propane, acetylene, helium, laser mixed gas, SiH<sub>4</sub>, SiH<sub>2</sub>Cl<sub>2</sub>, SiHCl<sub>3</sub>, SiCl<sub>4</sub>, NH<sub>3</sub>, CF<sub>4</sub>, NF<sub>3</sub>, SF<sub>6</sub>, HCL, N<sub>2</sub>O, doping mixed gas (TMB, PH<sub>3</sub>, B<sub>2</sub>H<sub>6</sub>) and other electronic gases.



SiCl <sub>4</sub>	NH <sub>3</sub>	NH <sub>3</sub>	CH <sub>3</sub> F	SiH <sub>4</sub>	Kr	H <sub>2</sub> S	WF <sub>6</sub>	F <sub>6</sub> +Cl <sub>2</sub>
4MS	C <sub>3</sub> F <sub>8</sub>	C <sub>3</sub> F <sub>8</sub>	TEOS	CH <sub>4</sub>	PH <sub>3</sub>	SF <sub>6</sub>	C <sub>2</sub>	HCl+Ne
CF <sub>4</sub>	C <sub>4</sub> F <sub>8</sub>	SiH <sub>2</sub>						TMB+H <sub>2</sub>
SiF <sub>4</sub>	C <sub>3</sub> H <sub>8</sub>	Cl <sub>2</sub>						He +As
BBr <sub>3</sub>	C <sub>3</sub> H <sub>6</sub>	DCE						Ge+Se
POCl <sub>3</sub>	N <sub>2</sub>	SO <sub>2</sub>						D+B
BCl <sub>3</sub>	D <sub>2</sub>	CO <sub>2</sub>						CO+NO
SiHCl <sub>3</sub>	CH <sub>2</sub> F <sub>2</sub>	HF						Ar+O <sub>2</sub>
TMAI	DMZn	DEZn						Xe+NO
AsH <sub>3</sub>	C <sub>2</sub> H <sub>4</sub>	C <sub>2</sub> H <sub>2</sub>	HBr	COS	Ar+O <sub>2</sub>			
GeH <sub>4</sub>	C <sub>2</sub> H <sub>6</sub>	B <sub>2</sub> H <sub>6</sub>	H <sub>2</sub> Se	GeCl <sub>4</sub>	Xe+NO			

SiCl <sub>4</sub>	NH <sub>3</sub>	NH <sub>3</sub>	CH <sub>3</sub> F	SiH <sub>4</sub>	Kr	H <sub>2</sub> S	WF <sub>6</sub>	F <sub>6</sub> +Cl <sub>2</sub>
4MS	C <sub>3</sub> F <sub>8</sub>	C <sub>3</sub> F <sub>8</sub>	TEOS	CH <sub>4</sub>	PH <sub>3</sub>	SF <sub>6</sub>	C <sub>2</sub>	HCl+Ne
CF <sub>4</sub>	C <sub>4</sub> F <sub>8</sub>	SiH <sub>2</sub>						TMB+H <sub>2</sub>
SiF <sub>4</sub>	C <sub>3</sub> H <sub>8</sub>	Cl <sub>2</sub>						He +As
BBr <sub>3</sub>	C <sub>3</sub> H <sub>6</sub>	DCE						Ge+Se
POCl <sub>3</sub>	N <sub>2</sub>	SO <sub>2</sub>						D+B
BCl <sub>3</sub>	D <sub>2</sub>	CO <sub>2</sub>						CO+NO
SiHCl <sub>3</sub>	CH <sub>2</sub> F <sub>2</sub>	HF						Ar+O <sub>2</sub>
TMAI	DMZn	DEZn						Xe+NO
AsH <sub>3</sub>	C <sub>2</sub> H <sub>4</sub>	C <sub>2</sub> H <sub>2</sub>	HBr	COS	Ar+O <sub>2</sub>			
GeH <sub>4</sub>	C <sub>2</sub> H <sub>6</sub>	B <sub>2</sub> H <sub>6</sub>	H <sub>2</sub> Se	GeCl <sub>4</sub>	Xe+NO			